| | Application No. | Applicant(s) | |
|---|--|--|----|
| Notice of Allowability | 10/076,005 | BAUDE ET AL. | |
| | Examiner | Art Unit | |
| | Jeffrie R. Lund | 1763 | |
| The MAILING DATE of this communication app All claims being allowable, PROSECUTION ON THE MERITS Is herewith (or previously mailed), a Notice of Allowance (PTOL-88 NOTICE OF ALLOWABILITY IS NOT A GRANT OF PATENT I of the Office or upon petition by the applicant. See 37 CFR 1.37 | S (OR REMAINS) CLOSED in 5) or other appropriate comm RIGHTS. This application is the second control of the se | n this application. If not included unication will be mailed in due course. TH | |
| 1. This communication is responsive to <u>amendments filed A</u> | pril 5 and 27, 2004. | | |
| 2. The allowed claim(s) is/are <u>1-7,9-35 and 53-60</u> . | | | |
| 3. \boxtimes The drawings filed on <u>14 February 2003</u> are accepted by | the Examiner. | | |
| 4. ☐ Acknowledgment is made of a claim for foreign priority of a) ☐ All b) ☐ Some* c) ☐ None of the: 1. ☐ Certified copies of the priority documents have 2. ☐ Certified copies of the priority documents have 3. ☐ Copies of the certified copies of the priority of International Bureau (PCT Rule 17.2(a)). * Certified copies not received: | ve been received. ve been received in Application | on No | 1e |
| Applicant has THREE MONTHS FROM THE "MAILING DATE noted below. Failure to timely comply will result in ABANDON THIS THREE-MONTH PERIOD IS NOT EXTENDABLE. | | a reply complying with the requirements | |
| 5. A SUBSTITUTE OATH OR DECLARATION must be sub- INFORMAL PATENT APPLICATION (PTO-152) which gi | mitted. Note the attached EXA ves reason(s) why the oath o | AMINER'S AMENDMENT or NOTICE OF declaration is deficient. | |
| 6. ☐ CORRECTED DRAWINGS (as "replacement sheets") mutual (a) ☐ including changes required by the Notice of Draftspe 1) ☐ hereto or 2) ☐ to Paper No./Mail Date (b) ☐ including changes required by the attached Examine Paper No./Mail Date Identifying indicia such as the application number (see 37 CFR each sheet. Replacement sheet(s) should be labeled as such in | rson's Patent Drawing Review r's Amendment / Comment or 1.84(c)) should be written on the | in the Office action of ne drawings in the front (not the back) of | |
| DEPOSIT OF and/or INFORMATION about the dep attached Examiner's comment regarding REQUIREMENT | | | |
| Attachment(s) 1. ☑ Notice of References Cited (PTO-892) 2. ☐ Notice of Draftperson's Patent Drawing Review (PTO-948) 3. ☐ Information Disclosure Statements (PTO-1449 or PTO/SB. Paper No./Mail Date 4. ☐ Examiner's Comment Regarding Requirement for Deposit of Biological Material | 6. Interview S Paper No./ /08), 7. Examiner's | formal Patent Application (PTO-152) ummary (PTO-413), Mail Date Amendment/Comment Statement of Reasons for Allowance | |
| | | Jeffrie R. Lund Primary Examiner Art Unit: 1763 | |

EXAMINER'S AMENDMENT

1. An examiner's amendment to the record appears below. Should the changes and/or additions be unacceptable to applicant, an amendment may be filed as provided by 37 CFR 1.312. To ensure consideration of such an amendment, it MUST be submitted no later than the payment of the issue fee.

Authorization for this examiner's amendment was given in a telephone interview with Lisa P. Fulton on June 7, 2004.

The application has been amended as follows:

Applicant has agreed to cancel non-elected claims 36-52.

2. The following is an examiner's statement of reasons for allowance: the elongated web of flexible polymeric film, and a deposition mask pattern formed in the film, wherein the deposition mask pattern defines deposition apertures that extend through the film that define at least a portion of an integrated circuit as claimed in claim 1; the second web of flexible polymeric film, wherein the second web of film defines a deposition mask pattern that defines at least a portion of an integrate circuit, the drive, and deposition apparatus as claimed in claim 21; the deposition mask pattern formed in a second and third web of polymeric film with a first and second deposition chamber as claimed in claim 53; the deposition mask pattern formed in a web of polymeric film with a stretching mechanism claimed in claim 54; the deposition mask pattern formed in a web of polymeric film with a first and second stretching mechanism and deposition chamber as claimed in claims 58 and 60 were not found in or suggested by the art.

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The use of deposition masks formed in a web is well known in the art as shown by Izu et al in US Patents 4,519,339 and 4,542,711. However, all of the prior art web masks are made of metal. Polymeric masks are known in the art as shown in Schwiebert et al, US Patent 5,539,153. However, these masks are small, the size of a single semiconductor wafer (i.e. less than about 13 inches), and held in place by a metal frame. There is no suggestion in the art that a deposition mask made from a web of polymeric film as claimed in the present claims would work (i.e. that a mask formed in a web of polymeric film would be strong enough to hold the pattern without distortion of the pattern (stretch), or allow the flow of the coating material only through the pattern). Therefore, no motivation was found to make a deposition mask from a web of polymeric film.

Any comments considered necessary by applicant must be submitted no later than the payment of the issue fee and, to avoid processing delays, should preferably accompany the issue fee. Such submissions should be clearly labeled "Comments on Statement of Reasons for Allowance."

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Jeffrie R. Lund whose telephone number is (571) 272-.

1437. The examiner can normally be reached on Monday-Thursday (6:30 am-6:00pm).

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Gregory Mills can be reached on (571) 272-1439. The fax phone number for the organization where this application or proceeding is assigned is 703-872-9306.

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Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

Jeffrie R. Lund Primary Examiner Art Unit 1763

JRL 6/7/04